

Never Stand Still

Faculty of Engineering

School of Chemical Engineering

## Project Background

### ❖ Cuprous Oxide (Cu<sub>2</sub>O):

- Earth abundant & non-toxic
- Ease in forming numerous **well-defined morphologies**
- p-type semiconductor with **favourable band potentials** for redox reactions

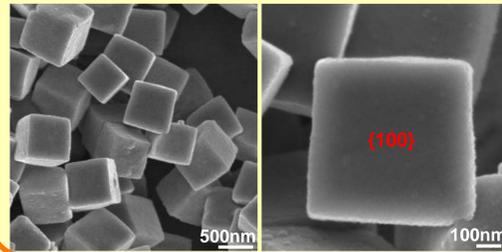
### ❖ Facet-engineering of Cu<sub>2</sub>O:

- Facet-dependent properties
  - ✓ Surface adsorption ability
  - ✓ Surface electronic band structure
  - ✓ **Surface defect density**
- Influence the intrinsic carrier dynamics

## Morphology and Structure

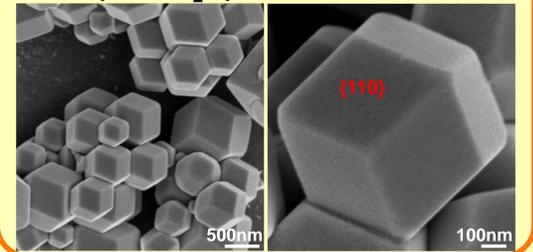
60 °C,  
no oleic acid

Cubic  
(CB-Cu<sub>2</sub>O)



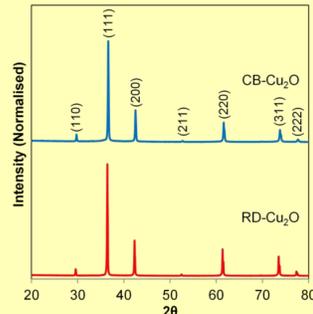
100 °C,  
12 mL oleic acid

Rhombic Dodecahedral  
(RD-Cu<sub>2</sub>O)



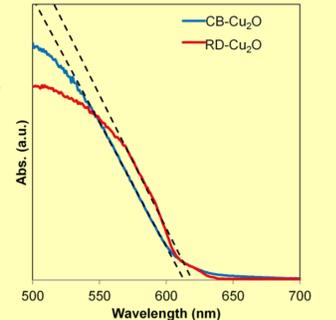
### XRD

- ❖ Similar XRD patterns
- ❖ Cubic crystalline Cu<sub>2</sub>O



### UV-Vis

- ❖ Comparable absorption band edge
- ❖ Bandgap: ~2.0 eV

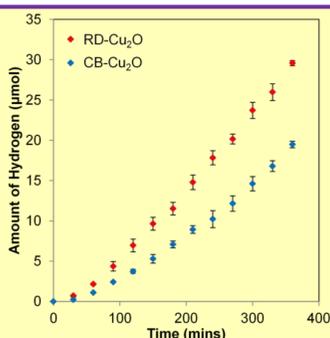


## Photoactivity

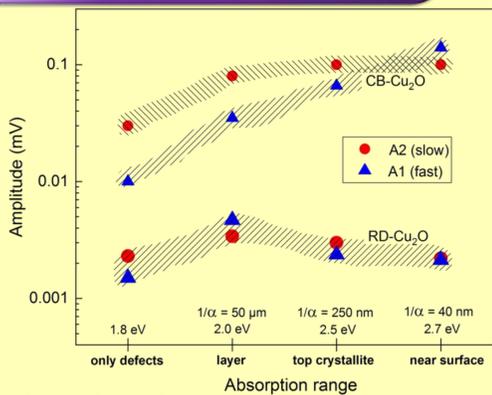
### Photocatalytic H<sub>2</sub> Evolution

RD-Cu<sub>2</sub>O: 29.6 μmol H<sub>2</sub>  
CB-Cu<sub>2</sub>O: 19.5 μmol H<sub>2</sub>

- ❖ RD-Cu<sub>2</sub>O shows better performances.



## Surface Photovoltage Measurement

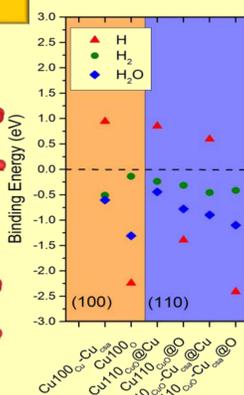
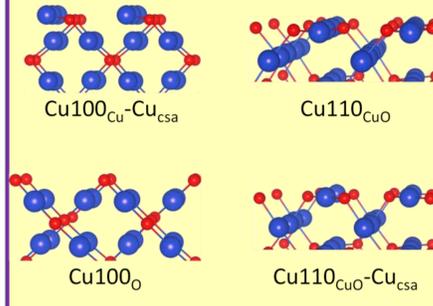


- ❖ RD-Cu<sub>2</sub>O: **weak SPV** due to lower defect density.
- ❖ RD-Cu<sub>2</sub>O: modulated charge distribution indicates **better charge transfer**.

## Factors Influencing Photoactivity

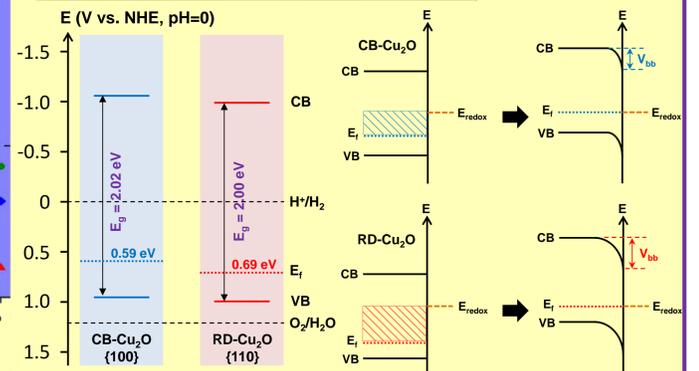
### Surface Absorption Ability

#### Thermodynamically stable facets



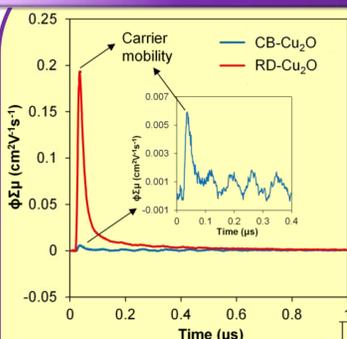
- ❖ Calculated using density of functional theory (DFT).
- ❖ By considering equal existence of these stable facets, surface adsorption ability of H, H<sub>2</sub> and H<sub>2</sub>O **could not be greatly differentiated**.

### Surface Electronic Structure



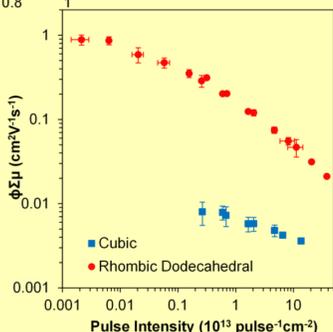
- ❖ **Proposed band structures** were identified by their bandgaps, valence bands computed from linear sweep voltammetry and valence XPS spectra.
- ❖ The larger band bending of RD-Cu<sub>2</sub>O indicates its **better charge transfer** when compared to CB-Cu<sub>2</sub>O.

## Time-resolve Microwave Conductivity Measurement



- ❖ RD-Cu<sub>2</sub>O show **higher carrier mobility**.
- ❖ Fitted carrier lifetime of RD-Cu<sub>2</sub>O is **longer**.

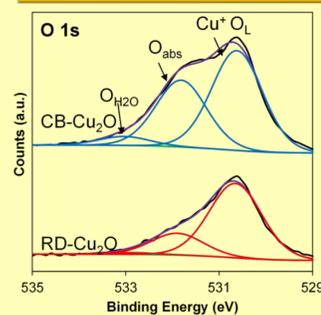
- ❖ RD-Cu<sub>2</sub>O consistently show **2 orders of magnitude higher carrier mobility** throughout different laser pulse intensity.



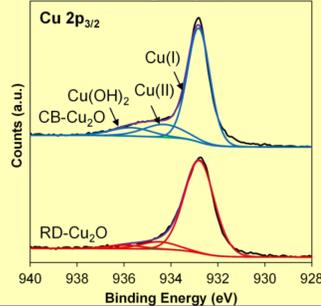
### TRMC:

- Highly sensitive contactless approach that utilizes nanosecond pulsed laser to **determine the carrier mobility and lifetime** of a semiconductor.
- Measures the change in reflected microwave power which is expressed as product of internal quantum efficiency ( $\phi$ ) and the sum of carrier mobility ( $\Sigma\mu$ ).

### Surface Defect Density

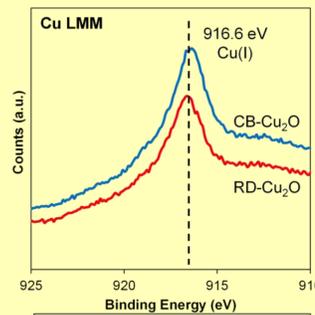


- ❖ O<sub>abs</sub> is associated to the oxygen vacancies.
- ❖ O 1s spectra show **higher amount of oxygen vacancies** in CB-Cu<sub>2</sub>O.

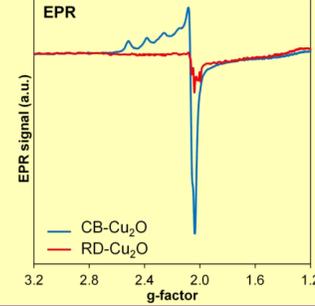


- ❖ Cu(II) indicates copper deficiency.
- ❖ Cu 2p spectra demonstrate **larger amount of copper defect (Cu<sup>2+</sup>)** in CB-Cu<sub>2</sub>O.

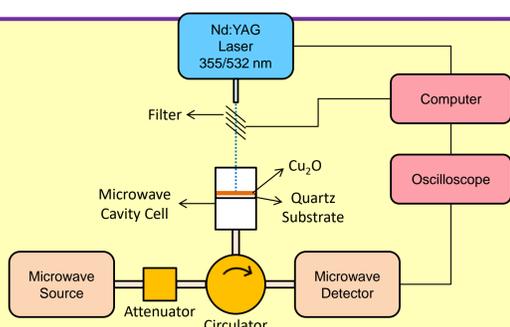
**CB-Cu<sub>2</sub>O has higher defect density than RD-Cu<sub>2</sub>O.**



- ❖ 916.6 eV corresponded to Cu<sub>2</sub>O is the only peak observed in Cu LMM auger spectra.
- ❖ **No CuO species**.



- ❖ Cu<sup>2+</sup> is paramagnetic species and can be detected by electron paramagnetic resonance (EPR) spectroscopy.
- ❖ **Intensified EPR signal** (g-value: 2.06) of CB-Cu<sub>2</sub>O indicates its higher amount of copper defect.



## Summary

- ❖ **RD-Cu<sub>2</sub>O > CB-Cu<sub>2</sub>O**
- ❖ Attributed to its **higher carrier mobility and better charge separation**, which is associated to its **lower surface defect density and different surface exposed facets**.
- ❖ This study shows that the **charge carrier dynamics** have deciding influence on photoactivity.